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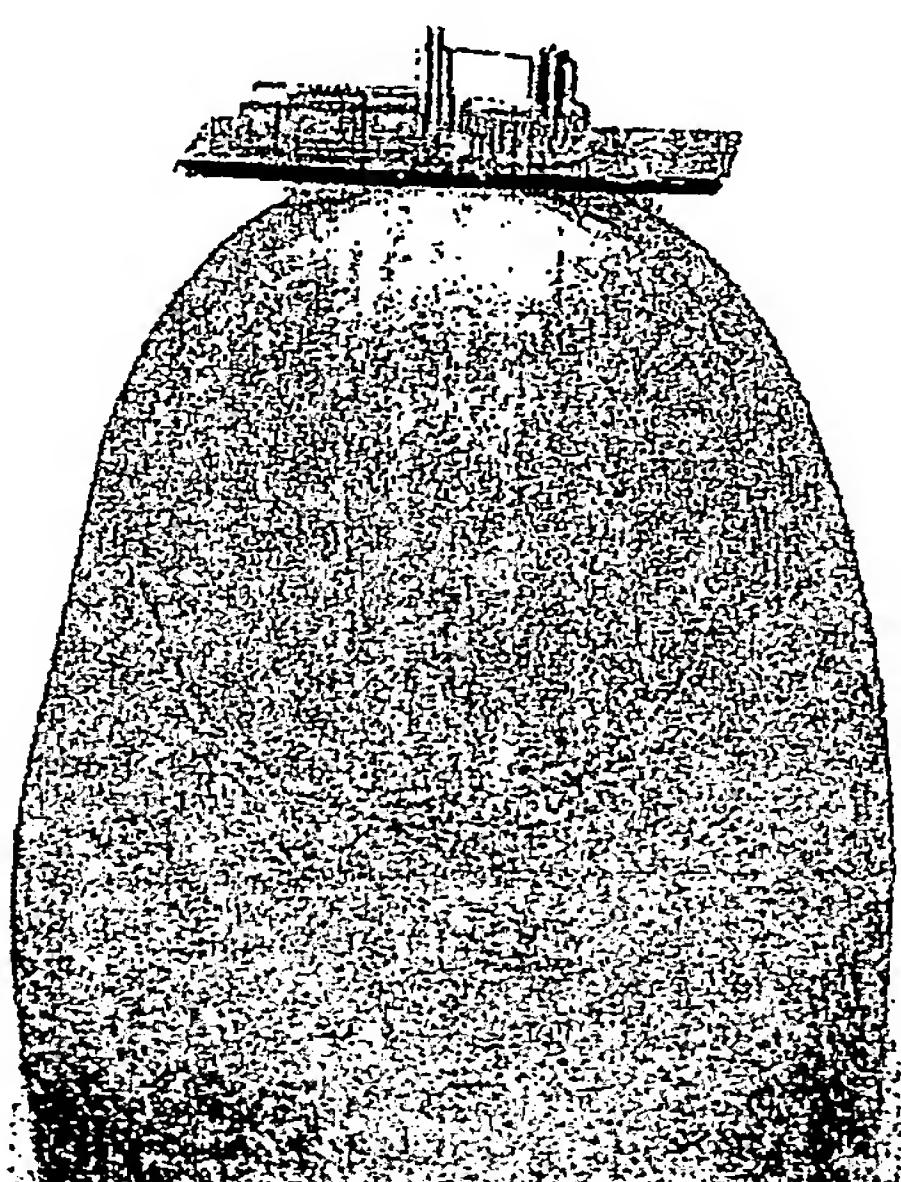
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(54) Title: IMPROVED LITHOGRAPHIC PROCESS



(57) Abstract: The present invention provides a lithographic process for producing high aspect ratio parts from an epoxy-type negative photoresist comprising the steps of: (i) irradiating a prebaked masked epoxy-type negative photoresist on a substrate with light at a total energy density of from 18,000 to 35,000mJ/cm², (ii) post-baking the exposed photoresist at elevated temperature, and (iii) developing the exposed photoresist in a solvent, wherein no more than 15 % of the energy density is contributed by light having a wavelength of 400nm or less. The invention also discloses a reciprocating micro-engine (10) comprising a cylinder (14), piston (12) and crankshaft made by the process.

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WO 2005/057289 A1